

APPLICATION  
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TITLE: SEMICONDUCTOR CIRCUIT MODULE AND METHOD  
FOR FABRICATING SEMICONDUCTOR CIRCUIT  
MODULES

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Semiconductor circuit module and method for fabricating semiconductor circuit modules

The present invention relates to a semiconductor  
5 circuit module and a method for fabricating semiconductor circuit modules.

Semiconductor devices, e.g. for use in computer systems or the memory devices thereof are usually constructed  
10 in module form. A conventional memory module essentially has two main groups of components. Firstly active and passive electrical circuit components and secondly a printed circuit board. The printed circuit board serves as a carrier for the circuit devices,  
15 provides connection elements such as conductor tracks and brings about a connection toward the outside.

Active electrical circuit devices, such as e.g. memory chips, are individual, packaged chips. The following  
20 functions are realized within the package: connection between contact pads of the chips to form a type of rewiring (leadframe, interposer board). This can be effected by means of bonding processes or by means of small solder balls as an interconnect element. This  
25 rewiring serves as a contact element for the next architectural level - connection to the application printed circuit board. Passive circuit components such as e.g. resistors, capacitors, etc. essentially serve for the external connection of the active circuit  
30 devices.

Electrical circuit components are soldered onto a circuit board during module assembly. The use of conventionally packaged active circuit devices results  
35 in a comparatively low component density and the thickness of the modules lies in the range of about 2 to 3 mm.

Figure 12 diagrammatically illustrates the population of a printed circuit board 29 with active and passive circuit devices 12, 13. Active circuit components 12, such as e.g. memory chips, are seated on an interposer substrate 30 provided with a connecting device 28, e.g. solder balls on soldering pads, for the purpose of electrical contact-connection to the printed circuit board 29. Passive circuit components 13, such as e.g. resistors, capacitors, etc., are likewise provided on the printed circuit board 29.

Figure 13 shows a customary multichip module having active and passive circuit devices 12, 13 on a printed circuit board 29. The active circuit devices or chips 12 are mounted on interposer substrates 30 using flip-chip technology (and additionally underfilled = adhesively bonded owing to the thermomechanical stability). The packages comprising chips 12 and interposer substrate 30 are fixed e.g. by means of solder balls 28 on the module carrier 29. Passive circuit devices 13 are soldered onto the circuit board 29, which have a large number of electrical connections such as conductor tracks between individual chips 12 or chips 12 and passive circuit elements 13. Such a customary arrangement thus has a high total thickness of at least  $d_1 + d_2 + d_3$  in the case of only one-sided placement, which leads to a module thickness of more than 2 mm, and furthermore results in a low component density since primarily the interposer substrate and conductor tracks have a large area requirement.

Therefore, it is an object of the present invention to provide a semiconductor circuit module and a method for fabricating semiconductor circuit modules whereby thin multichip modules with a high component density can be provided.

According to the invention, this object is achieved by means of the method for fabricating semiconductor circuit modules as specified in Claim 1 and by means of the semiconductor circuit module according to Claim 12.

5

The idea on which the present invention is based consists essentially in all the module components, both active and passive circuit devices, being premounted on a particular mounting plane - called wafer hereinafter 10 -, the packaging and the module assembly being combined in common process steps, and a module wafer being formed.

It is initially technically expedient to configure this 15 new mounting plane in the form of a previous silicon wafer. This enables easier access to the required further process steps of thin-film technology (metallization, photolithography,...), whose apparatuses already exist for the round wafers. However, the method 20 is not dependent on this form as a mounting plane. Larger rectangular areas are more effective and likewise conceivable.

In the present invention, the problem mentioned in the 25 introduction is solved in particular by virtue of the fact that a patterned connection layer is applied to a transfer substrate, to which layer active and/or passive circuit devices with contact areas pointing toward the transfer substrate are applied to the 30 patterned connection layer [sic] and the circuit devices are connected to one another by means of a filler at least between the circuit devices, whereupon the transfer substrate is removed and electrical connection devices for the selective contact-connection 35 of the contact areas of the circuit devices are applied.

On account of minimal gaps between the electrical circuit devices, a smallest possible area is taken up,

and the component density is thus maximized. Furthermore, it is possible in this way to produce ultrathin modules, e.g. with 100 µm or less, on account of the use of unpackaged active circuit devices, which  
5 have a minimum of volume, weight and electrical connection planes.

Since short connection lines occur on the modules, parasitic effects such as e.g. the capacitive coupling  
10 of an undesirable signal onto a connection line, turn out to be small, which results in a good electrical performance. Moreover, it is possible to dispense with a soldering process for fabricating the semiconductor circuit module.  
15

What is possible as a further advantage is a so-called cold and green processing or working of the semiconductor circuit module in the fabrication process, which is based on a functionally tested  
20 semiconductor device (known good die). It is also possible for modules to be stacked.

Advantageous developments and improvements of the respective subject matter of the invention are found in  
25 the subclaims.

In accordance with one preferred development, a protection device is applied at least over a part of the electrical connection device. As a result, the  
30 electrical connection device is mechanically protected from external influences.

In accordance with a further preferred development, a connecting device is provided in regions not covered by  
35 the protection device.

In accordance with a further preferred development, the patterned connection layer is applied in a printing process.

In accordance with a further preferred development, the circuit devices are arranged on the patterned connection layer in such a way that the electrical  
5 contact areas of the circuit devices are not located on the patterned connection layer.

In accordance with a further preferred development, the connection layer is not cured until after the circuit  
10 devices have been applied.

In accordance with a further preferred development, during and/or after the mechanical connection of the circuit devices to one another, an encapsulation of the  
15 circuit devices is applied.

In accordance with a further preferred development, the application of the filler and/or of the encapsulation is effected in a printing, molding (plastic  
20 injection-molding) or casting process.

In accordance with a further preferred development, the filler and/or the encapsulation is cured in a curing process before the transfer substrate is removed.  
25

In accordance with a further preferred development, the electrical connection layer is provided in at least one conductive layer and has conductor tracks in the x direction and/or conductor tracks in the y direction  
30 with an interposed insulating layer given a multilayered nature, which are in each case connected to one another selectively by means of vias.

In accordance with a further preferred development, a plurality of semiconductor circuit modules are fabricated in a parallel process at wafer level, which  
35 modules are separated into semiconductor circuit module strips or individual semiconductor circuit modules in a subsequent process step.

- In accordance with a further preferred development, the connection plane comprises a dielectric material such as a polymer, epoxy resin, adhesive, silicone or 5 polyimide.
- In accordance with a further preferred development, the filler comprises a non-conductive, curable material such as a polymer, adhesive or silicone. 10
- In accordance with a further preferred development, the encapsulation comprises the same material as the filler or the filler has additional properties. 15
- In accordance with a further preferred development, the protection device has a passivation layer made of a non-conductive material such as a polymer.
- In accordance with a further preferred development, the 20 semiconductor circuit module has at least one conductive passage from the front side to the encapsulated rear side, by means of which passage a further semiconductor circuit module can be connected, in particular by means of a conductive adhesive.
- In accordance with a further preferred development, the 25 connecting device has an edge connector or soldering pads provided with solder balls.
- In accordance with a further preferred development, the semiconductor circuit module has a total thickness of less than 200 µm, in particular a total thickness of about 100 µm. 30
- An embodiment of the invention is illustrated in the drawings and is explained in more detail in the description below. 35

In the figures:

- 5 Figures 1A, B show the diagrammatic illustration of a detail from an arrangement after a first method step in accordance with an embodiment of the present invention, Figure 1A illustrating a cross section and Figure 1B illustrating a plan view;
- 10 Figures 2A, B show the diagrammatic illustration of a detail from an arrangement after a further method step in accordance with an embodiment of the present invention, Figure 2A illustrating a cross section and Figure 2B illustrating a plan view;
- 15 Figures 3A, B show the diagrammatic illustration of a detail from an arrangement after a further method step in accordance with an embodiment of the present invention, Figure 3B illustrating the arrangement in accordance with Figure 3A after a directly succeeding method step;
- 20
- Figure 4 shows the diagrammatic illustration of a detail from an arrangement in the case of the method step of removal of the transfer substrate in accordance with an embodiment of the present invention;
- 25
- 30 Figure 5 shows a diagrammatic illustration of a detail from an arrangement after a further method step in accordance with an embodiment of the present invention;
- 35 Figures 6A, B show the diagrammatic illustration of a detail from an arrangement after a further method step in accordance with an embodiment of the present invention, Figure 6A illustrating a cross section

and Figure 6B illustrating a longitudinal section (turned 90°);

5           Figure 7 shows the diagrammatic illustration of a plan view for elucidating an embodiment of the present invention;

10          Figures 8A, B, C show the diagrammatic illustration of an arrangement for elucidating an embodiment of the present invention, Figure 8A illustrating a plan view, Figure 8B illustrating a cross section and Figure 8C illustrating a longitudinal section of the arrangement;

15          Figures 9A, B show the diagrammatic illustration of an arrangement in accordance with an embodiment of the present invention in longitudinal section, Figure 9A illustrating an individual module and Figure 9B illustrating two modules that are contact-connected to one another;

20          Figures 10A, B show the diagrammatic illustration of an arrangement in accordance with an embodiment of the present invention, Figure 10A illustrating a plan view and Figure 10B illustrating a longitudinal section;

25          Figures 11A, B show the diagrammatic illustration of an arrangement in accordance with a further embodiment of the present invention, Figure 11A illustrating a plan view and Figure 11B illustrating a longitudinal section;

30          Figure 12 shows a diagrammatic illustration for elucidating a customary arrangement;

Figure 13 shows the diagrammatic illustration of a customary multichip arrangement; and

5 Figures 14A, B show a flow diagram of the fabrication process for elucidating an embodiment of the present invention, Figure 14A illustrating a conventional fabrication method and Figure 14B illustrating a  
10 fabrication method in accordance with an embodiment of the present invention.

In the figures, identical reference symbols designate identical or functionally identical constituent parts.

15 Figure 1A illustrates a transfer substrate 10 e.g. made of glass, metal or a polymer, to which a patterned dielectric connection plane 11 is applied in a printing process. The dielectric connection plane 11, which, at  
20 this point in time, has not yet been cured and is thus still tacky, comprises e.g. a polymer, an epoxy resin, an adhesive, silicone or a polyimide.

25 Figure 1B shows the transfer substrate 10 with - applied thereto - individual connection areas 11 of the connection plane 11 in a plan view, the transfer substrate being embodied in rectangular fashion.

30 In Figure 2A, both active and passive circuit devices 12, 13 are applied to the transfer substrate 10 and the patterned connection plane 11. The circuit devices 12, 13 are applied to the connection plane in a predetermined position in such a way that the contact areas 12', 13' for the electrical contact-connection of  
35 the circuit devices 12, 13 point in the direction of the transfer substrate and fall on gaps or cutouts in the patterned connection plane 11. The active circuit devices 12 comprise functionally checked semiconductor devices, such as e.g. memory modules, which are

arranged exactly like the passive circuit devices 13 (resistors, capacitors, ...) e.g. in a die-bonding or pick and place process onto the uncured adhesive 11 on the transfer substrate 10.

5

The geometry, i.e. the assignment of the individual circuit devices to one another, is defined in this method step. The components 12, 13 are arranged as near as possible to one another in order to take up a 10 smallest possible area. The dielectric connection layer 11 is then cured e.g. thermally or by means of UV radiation, thereby fixing the position of the circuit devices 12, 13 with respect to one another.

15 Figure 2B shows the plan view of a connection plane 11 provided with circuit devices 12, 13 on the transfer substrate 10.

20 In Figure 3A, the gaps between the semiconductor devices 12 and the passive circuit devices 13 are filled with a filler 14. The filler 14 e.g. made of a polymer, an adhesive, silicone or the like is preferably applied or introduced in a printing or casting process and then cured.

25

Figure 3B illustrates an arrangement in accordance with Figure 3A in which an encapsulation 15 is provided over the circuit devices 12, 13 and the gaps between the circuit devices 12, 13, said gaps being provided with 30 filler 14. This rear-side encapsulation 15 may either be effected in the same step as the introduction of the filler 14 (in the same process device or chamber), but may also be effected afterward if the filler 14 is also intended to have additional properties which are not 35 provided for the encapsulation 15.

Figure 4 illustrates the removal of the transfer substrate 10 from the cured composite comprising patterned connection plane 11, active circuit

devices 12, passive circuit devices 13, gaps between the circuit devices 12, 13, said gaps being provided with filler 14, and the encapsulation 15. As a result, the contact areas 12', 13' of the circuit devices 5 12, 13 become accessible again.

In Figure 5, the composite in accordance with Figure 4 is provided with an electrical connection device 16 in a process step. The electrical connection device 16 10 comprises, for example, patterned, sputtered-on or electrochemically plated copper, nickel or gold conductor tracks which are applied between individual chips 12, chips 12 and passive circuit devices 13 and/or in a manner connected to a connecting device 19. 15 The patterned conductor tracks 16 run between the contact areas 12', 13' over the patterned dielectric connection layer 11.

The electrical connection device 16 is preferably a 20 double-layered line system with a dielectric layer between two patterned conductive layers, the conductive layers, one for connections or conductor tracks in the x direction, one for connections or conductor tracks in the y direction, being in electrical contact 25 selectively by means of vias in the dielectric layer, e.g. made of polyimide. Depending on the complexity of the module, it is necessary to form one or more electrical connection devices 16 in different planes for the selective electrical connection of the 30 components 12, 13 to one another.

Figure 6A shows the arrangement according to the invention in accordance with Figure 5, but with a passivation layer 17 over the electrical connection 35 device 16. The protection device 17 over the front side of the modules, which is applied such that it comprises a polymer e.g. in a printing process, covers the entire front side of the semiconductor circuit module 31 with the exception of a connecting device 19 or connecting

contacts, illustrated in Figure 6B. Figure 6B shows the arrangement in accordance with Figure 6A, but not in cross section, rather in a longitudinal section (turned through 90°).

5

Figure 7 illustrates a plurality of semiconductor circuit module strips 18 in a plan view which serves to illustrate rewiring devices 20 in the x direction and rewiring device 21 in the y direction as part of the 10 electrical connection device 16.

Figure 8A shows a semiconductor circuit module strip 18 with three different sections 22, 23, 24. The section 15 22 represents a passivated, covered module with a passivation layer 17, which has been omitted in the region 23. Essentially the chip side walls of the embedded chip can be seen in the section 24, since here no electrical connection layer 16 or dielectric connection plane 11 is applied.

20

Figure 9A illustrates the longitudinal section of a semiconductor memory module 31 provided with a conductive via 25, i.e. a plated-through hole from the front side of the module to the rear side of the 25 module. Such a plated-through hole 25 enables, for example, the electrical linking to a second semiconductor circuit module 31 by means of an electrically conductive adhesive 26. The mechanical connection between the two semiconductor circuit 30 modules 31 is preferably effected by means of an electrically non-conductive adhesive 27 in each case between the rear-side encapsulations 15 of the semiconductor circuit modules 31. Such a doubly stacked module comprising two semiconductor circuit modules 31 35 enables the component density to be increased further.

Figures 10A and B serve to illustrate a connecting device 19 in the form of a connecting strip or an edge connector.

Figure 11A shows a semiconductor circuit module strip 18 with an alternative connecting device 28 with respect to Figure 10. The solder balls 28 applied to 5 soldering pads represent an optimum of space saving in the x or y direction, but increase the module thickness. This results in a minimal area requirement essentially corresponding to the area of the active and passive circuit devices 12, 13.

10

A connecting device 19 by means of connecting contacts in the form of an edge connector can be produced in a simple manner in the formation of the electrical connection device 16 or the rewiring device 20, 21 if 15 the layer applied last has a hard contact surface, for example made of gold. If such an edge connector is arranged outside the area taken up by the active and passive circuit devices 12, 13 in an encapsulated section, then this increases the size of the module 20 construction.

Figure 14A illustrates a conventional process sequence in the fabrication of a semiconductor circuit module. The actual wafer fabrication is followed directly by 25 the wafer test before chips separated individually from the wafer are housed (first level packaging). This packaged component has to be checked again in respect of its functioning before it can be used to effect a module construction with further active and passive 30 circuit devices on a printed circuit board (second level packaging). A concluding module test provides information about the functionality of the semiconductor circuit device.

35 In contrast thereto, Figure 14B illustrates a diagrammatic process sequence in accordance with an embodiment of the present invention. Here, after wafer fabrication, during a comprehensive wafer test, a semiconductor device that has been positively tested

- and is thus deemed to be functional, in a further step, this tested semiconductor wafer module is processed further [sic]. This is followed by module formation, which has been described in detail with reference to
- 5 Figures 1A to 6B, before such a module likewise passes through a module test. This process sequence is based on knowledge of a good, i.e. tested semiconductor chip (known good die).
- 10 With this technology, very thin module wafers can be fabricated at low cost. Vias can be integrated into the encapsulation and an electrical connection from the front side to the rear side of the substrate/module is possible. This allows these wafers to be stacked to
- 15 form a three-dimensional module. If the semiconductor devices or chips and passive circuit devices are made very thin, it is possible to achieve flexible, pliant modules which can be adapted to a housing shape in a simple manner.
- 20 Although the present invention has been described above on the basis of preferred exemplary embodiments, it is not restricted thereto, but rather can be modified in diverse ways.
- 25 Although the parallel fabrication process for many semiconductor circuit modules on a round wafer for working by means of systems appertaining to thin-film technology is envisaged, rectangular wafer
- 30 configurations are also possible, which can be worked on machines used for flat screen displays or printed circuit boards. Further materials for the electrical/mechanical connection or linking of the active/passive circuit devices to one another are
- 35 likewise conceivable. Moreover, the invention is not restricted to the application possibilities mentioned.

List of reference symbols

- 10 Transfer substrate
- 11 Dielectric connection plane, e.g. made of epoxy resin
- 12 Tested semiconductor device (known good die)
- 12' Contact area of the tested semiconductor device
- 13 Passive circuit device, e.g. capacitor
- 13' Contact area of the passive circuit device
- 14 Filler, e.g. made of polymer, adhesive, silicone
- 15 Rear-side encapsulation, e.g. made of polymer, adhesive, silicone
- 16 Electrical connection device, e.g. in the x/y direction
- 17 Front-side passivation layer
- 18 Semiconductor circuit module strips
- 19 Connecting device, e.g. connecting contacts
- 20 Rewiring device, e.g. in the x direction between 12 and 13
- 21 Rewiring device, e.g. in the y direction with respect to 19
- 22 Passivated, covered module with passivation layer
- 23 Module section without passivation or covering
- 24 Section with visible embedded chip sidewalls
- 25 Conductive via, e.g. plated-through hole from the front side to the rear side of the chip
- 26 Electrical connection, e.g. made of conductive adhesive
- 27 Mechanical connection, e.g. made of non-conductive adhesive
- 28 Connecting device, e.g. solder balls on soldering pads
- 29 Printed circuit board
- 30 Interposer substrate for active/passive circuit devices
- 31 Semiconductor circuit module
- d1 Thickness of the circuit board, e.g. 800 µm to 1200 µm

- d2 Thickness of the connected interposer substrate,  
e.g. 400  $\mu\text{m}$  to 1000  $\mu\text{m}$
- d3 Thickness of the connected chip, e.g. greater than  
300  $\mu\text{m}$